

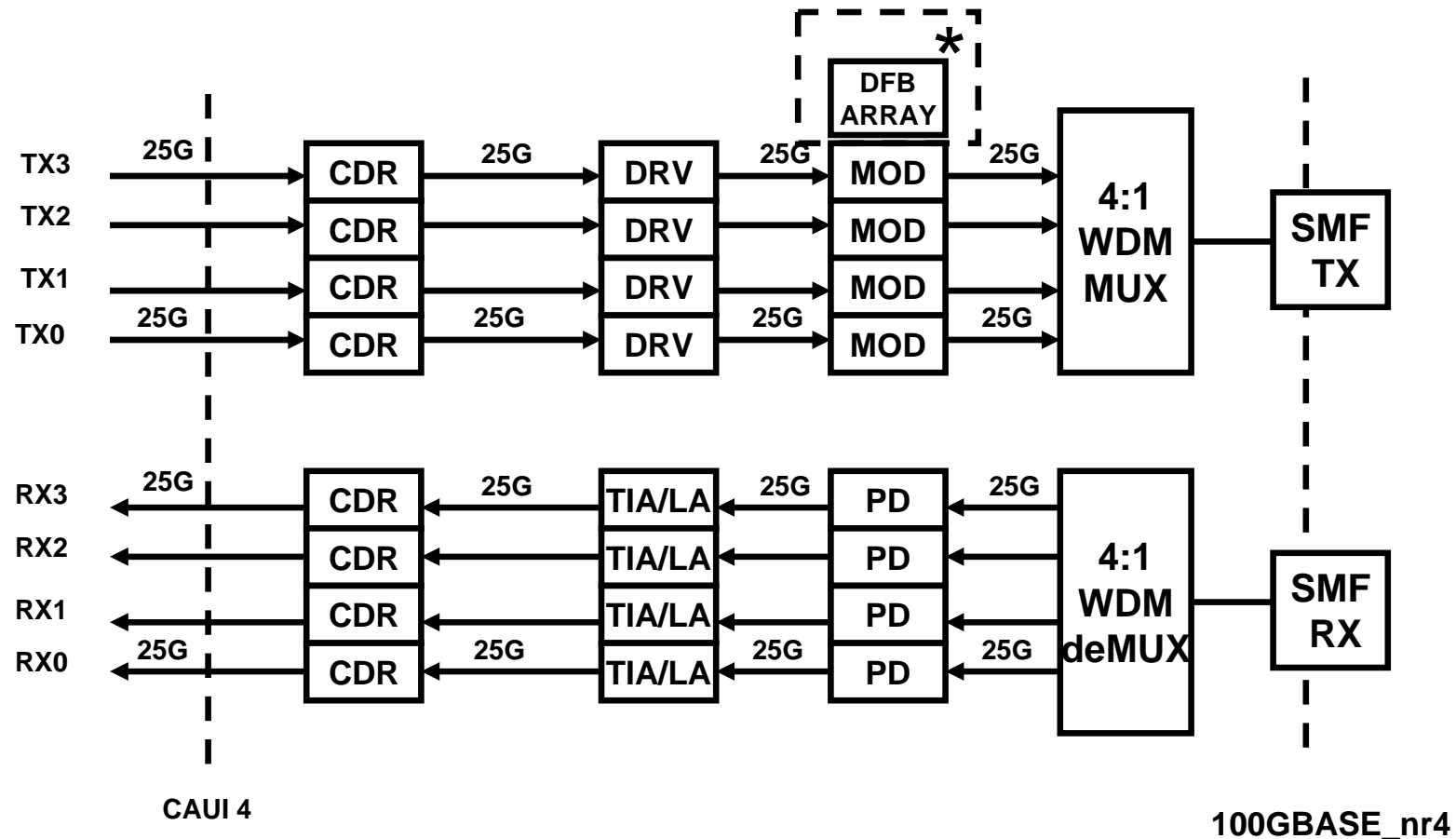
Considerations for WDM NRZ links : CMOS-Integrated Silicon Photonics case

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Introduction

- Step function cost reduction is needed
nowell_01_1111_NG100GOPTX.pdf
- Cost of SM solution is mostly defined by module cost
kipp_01_0112_NG100GOPTX.pdf
- PAM modulation is under consideration
bhoja_01_0112_NG100GOPTX.pdf
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 - Laser is a largest part of module cost
 - PAM modulation is using a single laser
- CMOS-integrated WDM NRZ is considered here
 - LAN WDM, Uncooled, Retimed
 - Link budget 3-4dB
 - Link length 2km

Single-die WDM NRZ block diagram

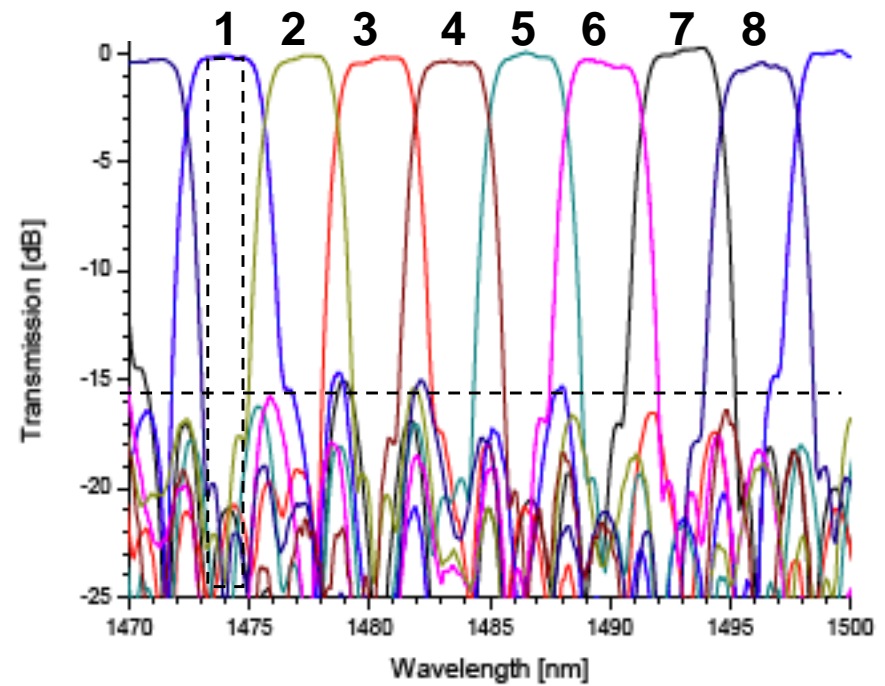
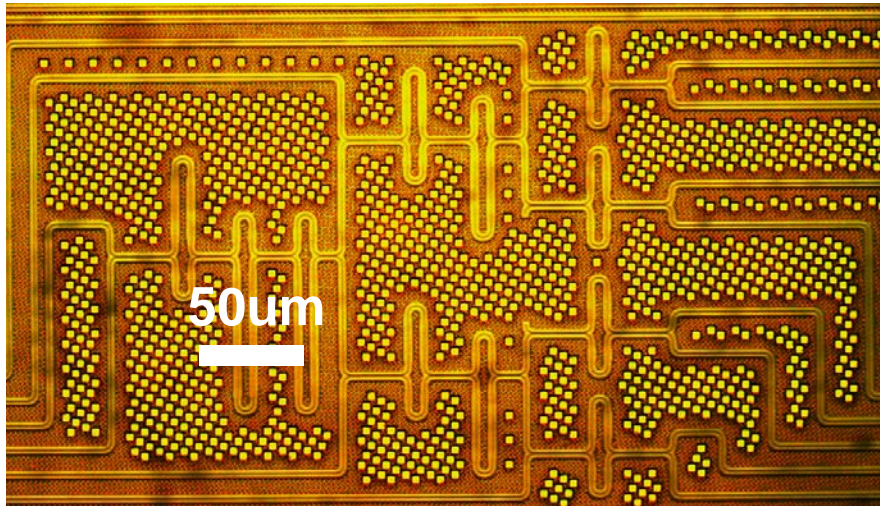


* DFB Array is a single die containing 4 DC DFB lasers

* Other implementations possible

Technical feasibility

- Example: 8 channel WDM at 1490nm
3-stage cascaded MZI lattice



- No add-on charges: same mask and same processing as CMOS FETs
 - High yield and uniformity → passive filtering – no active tuning required
-
- 4 channel LAN WDM at 1310nm is an easier task

Scaling of CMOS-integrated Photonics

- Scaling of Photonics

First technology node that can yield product-stable passive WDM is **the best**

- 193nm lithography can control the LER (line edge roughness) variation within 9 nm (3σ)
- Diffraction-limited scaled LAN WDM can be yielded by process control
- No need to individually tune phase delays to compensate for fabrication-induced phase errors
- Further scaling to advanced CMOS nodes would allow to control LER much better, however will not decrease the size of the WDM

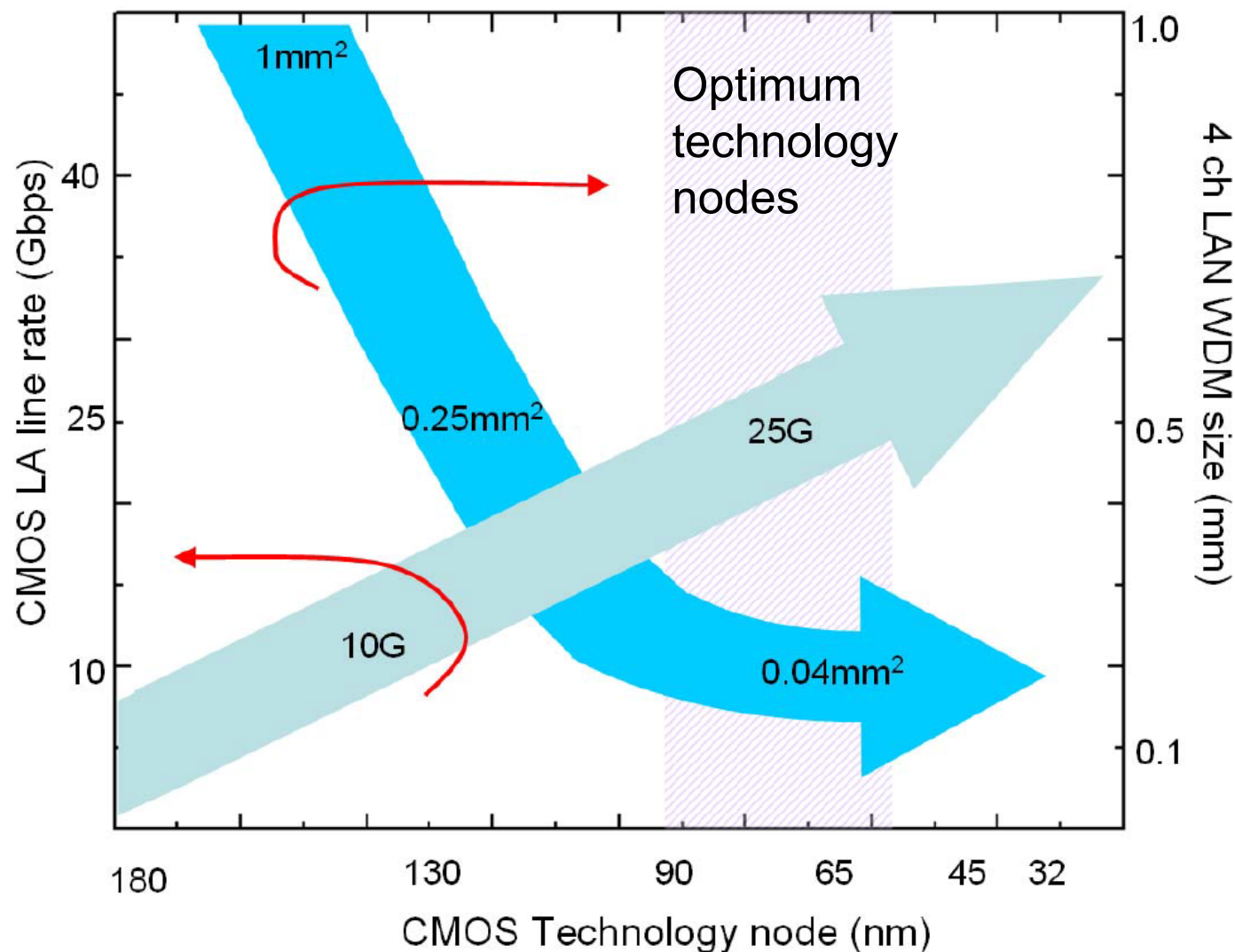
Scaling of CMOS-integrated Photonics

- Scaling of CMOS AMS circuits

First technology node that can yield product-stable 25/28Gbps AMS circuits including drivers, amps, CDR, etc. is **the best**

- Advanced CMOS nodes will have higher bandwidth
- However scaling of AMS circuits is not following the same trend as digital scaling: much less power and area savings
- Significantly increased NRE, mask/step charges for advanced nodes

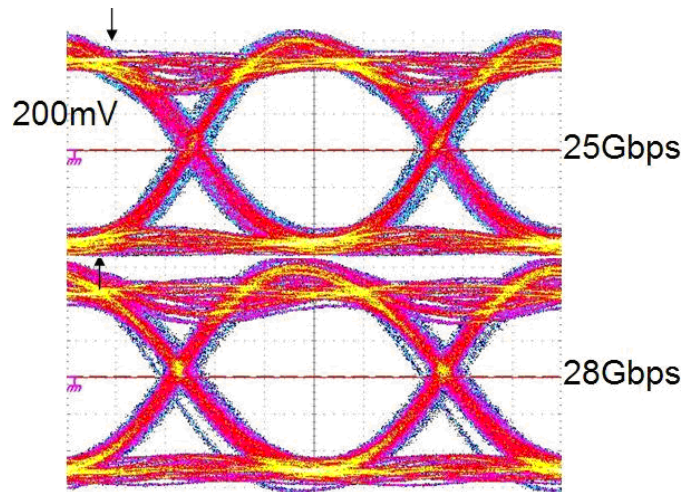
Choice of CMOS technology node



IEEE Comm. Mag. , February 2012, Y.Vlasov "Si nanophotonics for Computercom beyond 100G"

Feasibility demonstrations

- RX

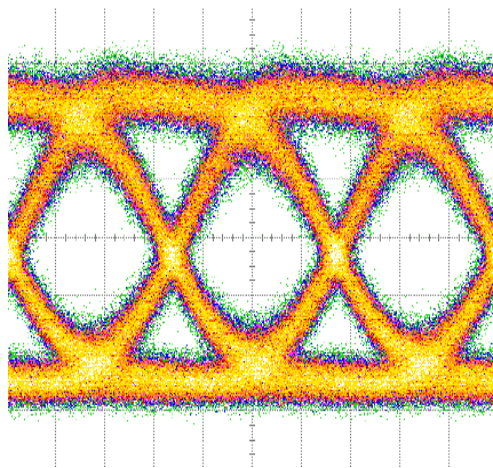


Measured 3.5pJ/bit @28Gbps

4ch@25Gbps = 350mW

Error-free (10^{-12} BER) up to 40Gbps

- TX



Ring modulator measured 100fJ/bit@25Gbps

Modulator driver measured 2pJ/bit@25Gbps

4ch@25Gbps = 200mW

Considerations for cost analysis

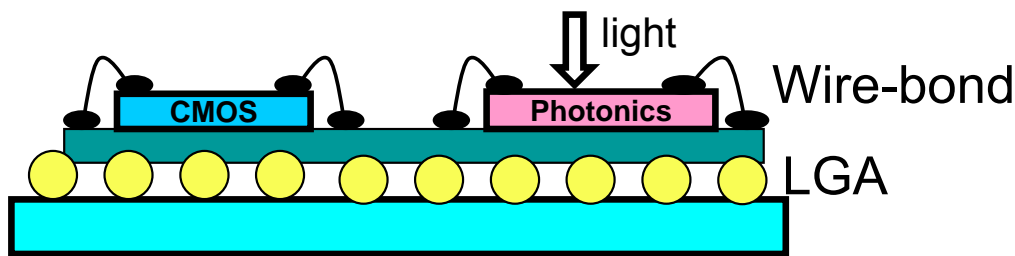
- Optical module cost analysis must include:
 - BOM (number / cost of components)
 - Assembly/packaging cost
 - Testing
- BOM for WDM CMOS transceiver
 - WDM CMOS Transceiver die * 1 (area 5x5mm²)
 - InP laser array die 1 (area 1x0.5mm²)
 - Fiber connector interface 1
 - Laminate 1

* Trivia: Integration of multiple optical and electrical components into a single CMOS die significantly decrease cost

Packaging and Testing

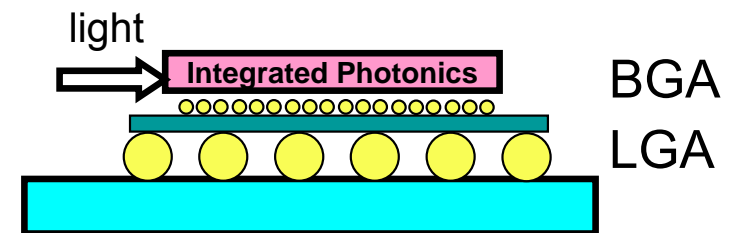
- Implementation of WDM transceiver in CMOS allows to utilize **packaging** practices of microelectronics industry

Traditional optoelectronics approach



BOM ↓
 Packaging ↑
 Testing ↑

Traditional microelectronics approach



BOM ↓
 Packaging ↓
 Testing ↓

- Implementation of WDM transceiver in CMOS allows to utilize **testing** practices of microelectronics industry
 - Wafer-scale testing in the middle of CMOS line
 - Wafer-scale system test at the end of CMOS line
 - Module test after packaging of best-known die

Considerations on WDM uncooled operation

- LAN WDM with flat-top
 - Operation within 40°C pp
- DC DFB laser
 - Usual temperature constraints for 25Gbps DML DFB are not very relevant for DC DFB
 - Main concern for DC DFB:
 - Variation of slope efficiency
 - Variation of laser wavelength
 - Both can be addressed by on-chip track-and-lock control circuitry
- Case temperature control vs die temperature control

Summary

- WDM NRZ CMOS-integrated single-chip TRX solution is considered
- Presented considerations on cost reductions looks promising
- Rigorous RCA analysis is required
- Feasibility requires further investigation